

**Project no: PN-II-ID-PCE-2011-3-0522: « Giga and terra-watt laser interaction with carbon, tungsten and beryllium films »**

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**Scientific report (Abstract)**

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**In the frame of Stage 1: “C, W and Be coatings interaction with the pulsed laser beam in vacuum. Coatings characterization before and after laser beam interaction experiment”, were performed deposition using thermionic vacuum arc method of a set of W and C layers. The deposition records and the characterization results are presented:**

**A. W deposition**

Substrate: 4x graphite substrates of 12 mm x16 mm

5x silicon substrates of 12 mm x14 mm

The correction factor used to set the quartz monitor was calculated using the following formula:

$$f_{correction} = \left( \frac{d_{X-quartz}}{d_{X-probes}} \right)^2$$

Using the above formula and sample-cathode distance was obtained a 1.396 factor.

|                               |                               |
|-------------------------------|-------------------------------|
| d <sub>W-quartz</sub><br>(cm) | d <sub>W-probes</sub><br>(cm) |
| 26                            | 22                            |
| f <sub>w</sub> =1.396         |                               |

**The coating were performed using the following parameters:**

| Nr. | $U_a(\text{kV})$ | $I_a(\text{A})$ | $I_f(\text{A})$ | P<br>(Torr)          | Thickness<br>(nm) | Time<br>(min) |
|-----|------------------|-----------------|-----------------|----------------------|-------------------|---------------|
| 1   | 0.75             | 1.9             | 42              | $1.5 \times 10^{-5}$ | 10                | 3             |
| 2   | 1.2              | 2               | 41              | $1.4 \times 10^{-5}$ | 30                | 12            |
| 3   | 1.2              | 2               | 41.5            | $1.5 \times 10^{-5}$ | 50                | 18            |
| 4   | 1.2              | 2               | 43              | $1.2 \times 10^{-5}$ | 100               | 33            |
| 5   | 1.4              | 1.9             | 44.5            | $1.2 \times 10^{-5}$ | 150               | 48            |
| 6   | 1.8              | 1.8             | 44.6            | $9.6 \times 10^{-6}$ | 180               | 57            |

$T_{\text{substrate}} = 600^\circ\text{C}$

**TOTAL deposition time = 64min**

**TOTAL thickness = 200nm**

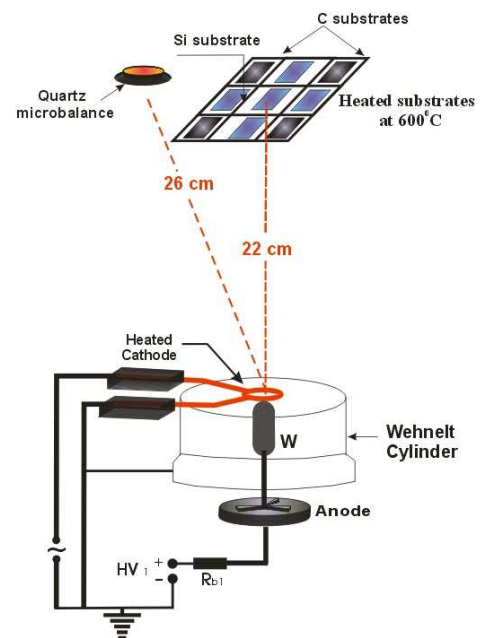


Fig.1 The set-up used for W deposition

## B. C deposition

Substrate: 4x graphite 12x16 (the previous W coated substrates)

5x Si 12x15

|                       |                       |
|-----------------------|-----------------------|
| $d_{\text{C-quartz}}$ | $d_{\text{C-probes}}$ |
|-----------------------|-----------------------|

Quartz correction factor

$$f_{correction} = \left( \frac{d_{X-quartz}}{d_{X-probes}} \right)^2$$

|            |      |
|------------|------|
| (cm)       | (cm) |
| 25         | 23   |
| $f_w=1.18$ |      |

**Deposition parameters:**

| Nr. | U <sub>a</sub> (kV) | I <sub>a</sub> (A) | I <sub>f</sub> (A) | P<br>(Torr)          | Thickness<br>(nm) | Time<br>(min) |
|-----|---------------------|--------------------|--------------------|----------------------|-------------------|---------------|
| 1   | 1.3                 | 1.8                | 37                 | 1.5x10 <sup>-5</sup> | 100               | -             |
| 2   | 1.5                 | 1.8                | 37                 | 1.5x10 <sup>-5</sup> | 200               | 2             |
| 3   | 1.4                 | 1.9                | 38.3               | 1.5x10 <sup>-5</sup> | 500               | 6             |
| 4   | 1                   | 2                  | 38                 | 1.5x10 <sup>-5</sup> | 830               | 11            |
| 5   | 0.8                 | 2.4                | 40                 | 1.5x10 <sup>-5</sup> | 1000              | 14            |
| 6   | 0.7                 | 2.6                | 39                 | 1.5x10 <sup>-5</sup> | 1350              | 18            |
| 7   | 0.9                 | 2.5                | 39.4               | 1.5x10 <sup>-5</sup> | 1950              | 28            |

T<sub>substrate</sub>=600<sup>0</sup>C

**TOTAL deposition time = 37min**

**TOTAL thickness = 2500 nm**

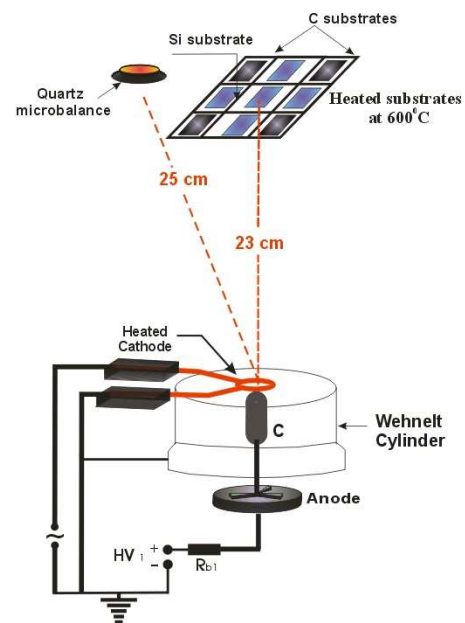


Fig.2 Carbon deposition set-up

The film structure is presented in Fig.3

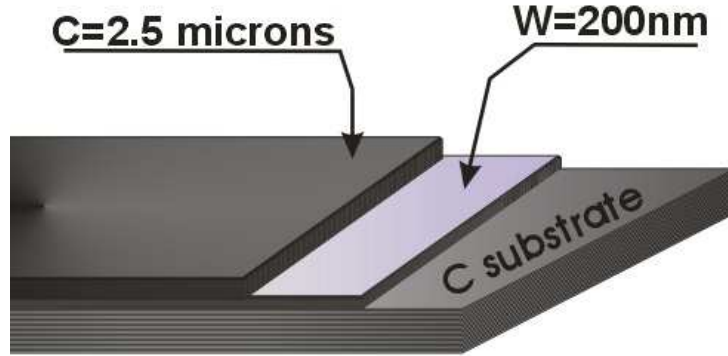


Fig.3 W+C multilayer thin film structure

#### D. Irradiation of the prepared samples: plasma plume emission spectra.

Using the terawatt laser system (Tewalas),  $20\text{-}30 \times 10^{-15}$  s pulse duration, 400-450 mJ pulse energy, were irradiated the prepared samples.

The spectra recorded in the 10-22 nm domain from 10 successive pulses in the same location on the sample.

Was observed that after 2 pulses appears the emission corresponding to the W element, and slowly disappear. (Fig.4)

Fig. 5 shows the emission in a zone where C lines does not exist, but only a cvasi continue W emission for all 10 successive pulses

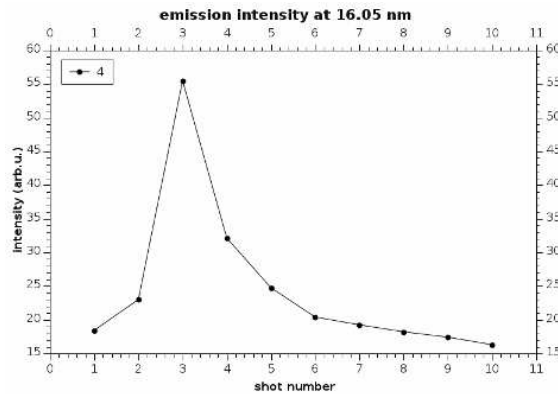


Fig. 4. Emission intensity of the W peak at 16.05 nm

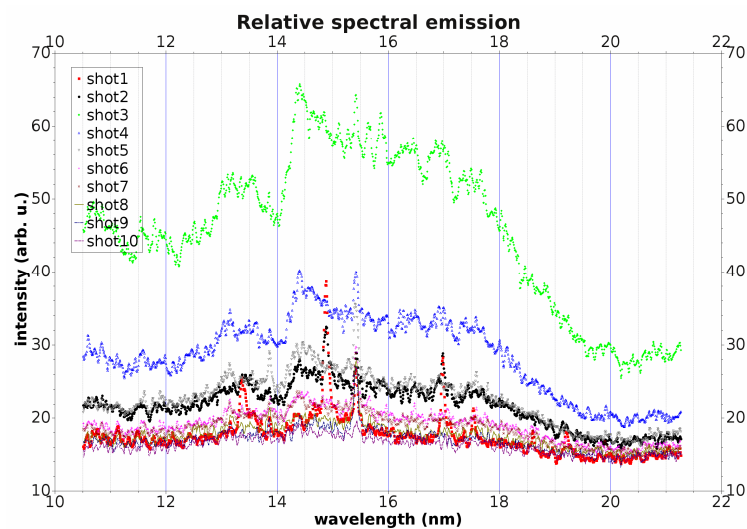


Fig.5 The emission spectra in the 10-22 nm range.

### E. Optical microscopy investigation

Using a high resolution optical microscope, the wear produced by the laser shot is presented in Fig. 6

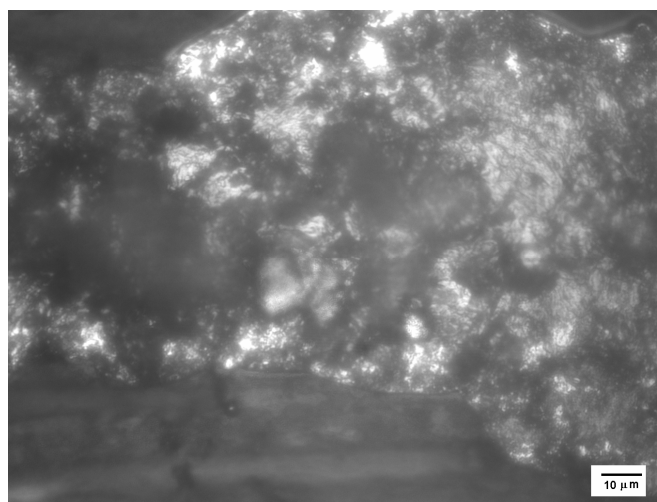


Fig.6. Wear produced by the laser shots on the prepared multilayer W – C film

Using SEM, EDS and Raman spectroscopy, the samples will be characterized further.

Project Director,

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